

**Amendments to the Abstract**

Please replace the abstract at page 33 with the following replacement abstract:

Described are process control methods for spin-coating, and apparatuses and devices incorporating the same, wherein the method is useful for application of developer solution to a substrate, and wherein the process control method includes one or more features of: interrupted serial process control using an interrupt signal from a hardware or a software component, an interrupt service routine, and a multiple process commands initiated at durations measured in parallel from an earlier process event.